

Docket No. 219587US90



DPU

2851/83
(C)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN RE APPLICATION OF: Masato HAMATANI, et al.

SERIAL NO: 10/072,866

GAU: 2851

FILED: February 12, 2002

EXAMINER: FULLER, R.

FOR: SPECIFICATION DETERMINING METHOD, PROJECTION OPTICAL SYSTEM MAKING METHOD AND ADJUSTING METHOD, EXPOSURE APPARATUS AND MAKING METHOD THEREOF, AND COMPUTER SYSTEM

INFORMATION DISCLOSURE STATEMENT UNDER 37 CFR 1.97

COMMISSIONER FOR PATENTS
ALEXANDRIA, VIRGINIA 22313

SIR:

Applicant(s) wish to disclose the following information.

REFERENCES

- The applicant(s) wish to make of record the references, some of which are cited in the U.S. Office Action for the co-pending application No. 10/608,032, the attached International Search Report for the co-pending application No. 10/608,032, the attached European Search Report, the attached Australian Search Report or the attached Australian Written Opinion, listed on the attached form PTO-1449. Copies of the listed references are attached, where required, as are either statements of relevancy or any readily available English translations of pertinent portions of any non-English language references.
- A check or credit card payment form is attached in the amount required under 37 CFR §1.17(p).

RELATED CASES

- Attached is a list of applicant's pending application(s) or issued patent(s) which may be related to the present application. A copy of the patent(s), together with a copy of the claims and drawings of the pending application(s) is attached along with PTO 1449.
- A check or credit card payment form is attached in the amount required under 37 CFR §1.17(p).

CERTIFICATION

- Each item of information contained in this information disclosure statement was first cited in any communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of this statement.
- No item of information contained in this information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign application or, to the knowledge of the undersigned, having made reasonable inquiry, was known to any individual designated in 37 CFR §1.56(c) more than three months prior to the filing of this statement.

DEPOSIT ACCOUNT

- Please charge any additional fees for the papers being filed herewith and for which no check or credit card payment is enclosed herewith, or credit any overpayment to deposit account number 15-0030. A duplicate copy of this sheet is enclosed.

08/04/2004 WABDEL1 00000130 10072866

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Respectfully submitted,

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Form PTO 1449 (Modified) LIST OF REFERENCES CITED BY APPLICANT				ATTY DOCKET NO. 219587US90	SERIAL NO. 10/072,866		
				APPLICANT Masato HAMATANI, et al.			
				FILING DATE February 12, 2002		GROUP 2851	
				U.S. PATENT DOCUMENTS			
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
	AA	6,248,486	06/19/2001	DIRKSEN, et al.			
	AB	2002/0008869 A1	01/24/2002	VAN DER LAAN, et al.			
	AC	2002/0036758 A1	03/28/2002	DE MOL, et al.			
	AD	2002/0191165 A1	12/19/2002	BASELMANS, et al.			
	AE	5,978,085	11/02/1999	SMITH, et al.			
	AF	6,078,554	06/20/2000	OOTAKI, et al.			
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	AH	6,100,978	08/08/2000	NAULLEAU, et al.			
	AI	2002/0001071 A1	01/03/2000	NOMURA, et al.			
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	AK	6,329,112	12/11/2001	FUKUDA, et al.			
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION		
					YES	NO	
	AK	1 160 626	12/05/2001	EUROPE			
	AL	WO 00/31592	06/02/2000	WIPO			
	AM	1 128 217	08/29/2001	EUROPE			
	AN	10-154657	06/09/1998	Japan (w/ English abstract)			x
	AO	2000-121491	04/28/2000	Japan (w/ English abstract)			x
	AP	WO 99/60361	11/25/1999	WIPO (w/ English abstract)			x
	AQ	1 079 223	02/28/2001	EUROPE			
	AR	11-118613	04/30/1999	Japan (w/ English abstract)			x
	AS	6-235619	08/23/1994	Japan (w/ English abstract)			x
	AT	5-296879	11/12/1993	Japan (w/ English abstract)			x
	AU	2000-47103	02/18/2000	Japan (w/ English abstract)			x
	AV	2000-331923	11/30/2000	Japan (w/ English abstract)			x
	AW	11-233424	08/27/1999	Japan (w/ English abstract)			x
	AX	198 20 785 A1	10/21/1999	Germany			x
	AY	2000-121491	04/28/2000	Japan (w/ English abstract and translation)	x		
	AZ	2000-146757	05/26/2000	Japan (w/ English abstract and machine translation)	x		
	BA	2000-266640	09/29/2000	Japan (w/ English abstract and machine translation)	x		
	BB	WO 00/55890	09/21/2000	WIPO (w/ English abstract)			x
	BC	2001-230193	08/24/2001	Japan (w/ English abstract and machine translation)	x		
	BD	1 160 626 A1	12/05/2001	Europe			
	BF	1 355 140 A1	10/22/2003	Europe (corresponding to U.S. Application 10/608,032)			
	BG	1 359 608 A1	11/05/2003	Europe			
	BH	WO 02/50506 A1	06/27/2002	WIPO (w/ English abstract)			x
					█ Additional References sheet(s) attached		
Examiner				Date Considered			
*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							



Form PTO 1449 (Modified)		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	
LIST OF REFERENCES CITED BY APPLICANT		ATTY DOCKET NO.	SERIAL NO.
		219587US90	10/072,866
		APPLICANT Masato HAMATANI, et al.	
FILING DATE February 12, 2002		GROUP 2851	
OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, etc.)			
	AAA	Winter 1998 MICROLITHOGRAPHY WORLD pages 11-20 Authors: Donis G. Flagello and Bernd Geh Title: "The influence of lens aberrations in lithography"	
	AAB	Journal of Vacuum Science & Technology B: Microelectronics Processing and Phenomena, American Vacuum Society, New York, NY, US, vol. 16, no. 6, November 1998 (1998-11) pages 3435-3439 Authors: K. Goldberg, et al. Title: "High-accuracy interferometry of extreme ultraviolet lithographic optical system"	
	AAC	SPIE Microlithography Seminar, pages 1-14 Authors: Donis G. Flagello, et al. Title: "TOWARDS A COMPREHENSIVE CONTROL OF FULL-FIELD IMAGE QUALITY IN OPTICAL PHOTOLITHOGRAPHY"	
	AAD		
	AAE		
	AAF		
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	AAK		
	AAL		
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	AAN		
	AAO		
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	AAQ		
Examiner			Date Considered
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